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Group Art Unit: 2818
Examiner: Chuong A. Luu
Confirmation No.: 6341

In Re PATENT APPLICATION Of:

Applicant: Noriko Tomita et al.

Serial No.: 10/660,490

Filed: September 12, 2003

For: SEMICONDUCTOR SUBSTRATE
SURFACE PROTECTION METHOD

Attny Ref.: OHG 135

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) RESPONSE
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September 4, 2006Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This paper is in response to the Official Action mailed on June 15, 2006. No fee is due. Please charge our Deposit Account No. 18-0002 any fees needed to enter this paper, and please advise us accordingly. It is noted that no petition is required because of the authorization to charge, but this paper is a petition for extension of time if needed.

An interview request form is attached. The Examiner is invited to telephone the undersigned attorney at 717-426-1664 to arrange the interview.

Please consider the following remarks:

§ 112, First Paragraph: Claims were rejected for "leaving the substrate to stand in air," which is asserted to be new matter. Reconsideration is requested.

The Examiner does not explain the rejection, but it appears that the earlier citations were not acceptable. The Applicants now further point to page 3, lines 4-8; the Abstract at line 3; and